

3D PRINTING CONFERENCE INNOVATION, Modelling, Application & Implementation

October 05-06, 2017 | Las Vegas, USA

Femto-second laser lithography of 2D and 3D nanostructures

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N ext-gen technologies will rely heavily on ability to go in third or even fourth dimension. Additive manufacturing of 3D at large scale have been demonstrated extensively in the past but micron size or below has been elusive till date. Strong absorption of materials below infrared wavelength makes 3D patterning impossible using any standard lithography process. Femto-second laser working in IR range utilize simultaneous absorption of two photon for realizing 3D nanostructures.

Speaker Biography

Shobha Shukla is an Assistant Professor in the Department of Metallurgical Engineering and Materials Sciences at the Indian Institute of Technology, Bombay, India. She obtained her doctoral degree at the State University of New York/SUNY Buffalo, USA. Subsequently she worked as a postdoctoral fellow at the School of Engineering and Applied Sciences Harvard University, Cambridge, Massachusetts, USA.

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